First Results on 3D Pixe Pixel detectors in the innermost layers of the future HL-LHC experiments at CERN (Geneva, Switzerland) will have to survive Sensors Interconnected with high tracking efficiency up to a fluence in excess of 2x10¹ neq/cm², while preserving high tracking efficiency. The total to RD53A Readout Chip active sensor thickness should be small enough to keep both the bias voltage and the power dissipation after irradiation to a after Irradiation to manageable level, but at the same time allowing for a 1x1016 neq/cm² reasonable amount of collected charge to reach full hit

Marco Meschini

for the CMS Tracker Collaboration INFN Firenze, Italy marco.meschini@cern.ch

G. F. Dalla Betta^a, R. Mendicino^a, M. Boscardin^b a INFN TIFPA and University of Trento, Italy

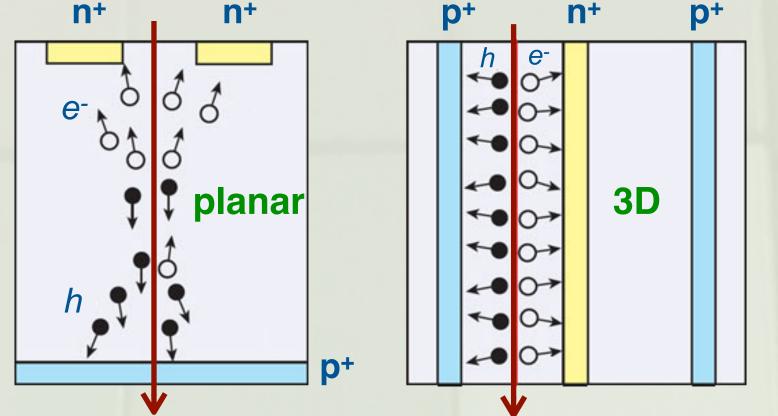
The 3D Columnar Pixel Sensors

The 3D sensors¹ are fabricated in FBK foundry in Trento; they are developed in a joint collaboration program with INFN (Istituto Nazionale di Fisica Nucleare, Italy). The substrates selected for the 3D sensors are p-type Si-Si Direct Wafer Bond (DWB) or SOI (Silicon On Insulator). Handle wafer is 500µm thick low resistivity Czochralski (CZ). FBK active devices are implanted on Float Zone (FZ), high resistivity (>3000 Ohm cm), 130µm thick wafer.

3D pixels, satisfying all of the above requirements, are very **NFN** good candidates for the upgrade of Inner Trackers

Why 3D pixel?

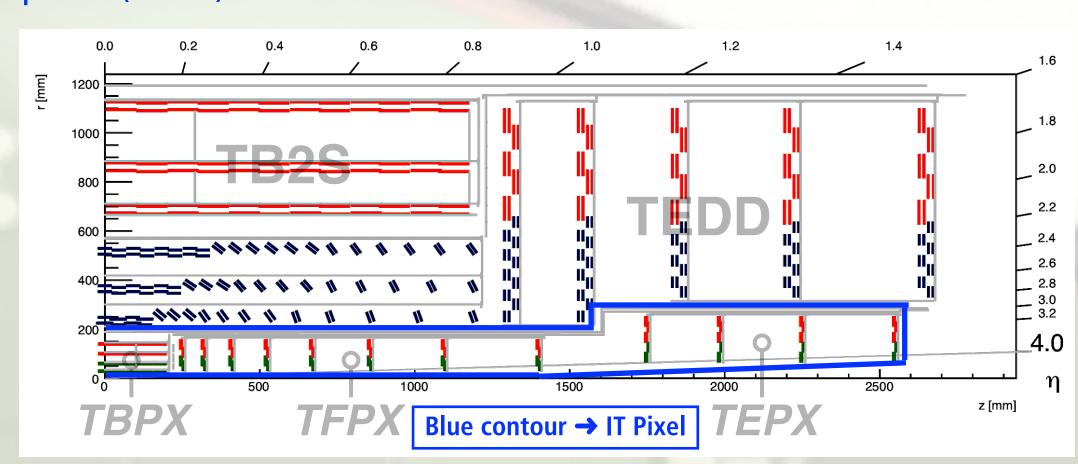
3D vs Planar Pixels



Artist's view of a 3D For the same sensor pitch and 150µm thickness, a traversing

Layout of the proposed CMS Tracker at HL-LHC

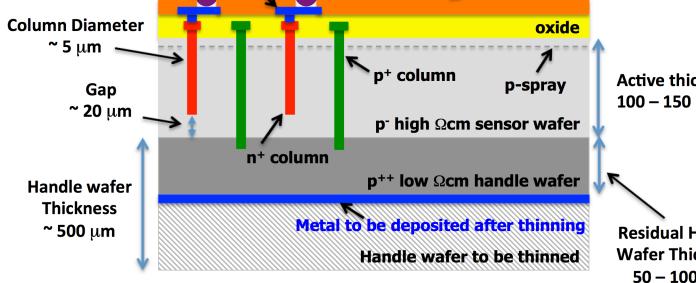
Inner Tracker (IT): 4.9m², 2G pixels; innovative tilted geometry in the inner barrel. Outer Tracker (OT): strip/strip (2S) and strip/macropixel (PS) modules, 13296 in total, 192m2, 42M strips, 170M macropixels (25m2).



Module Construction and Test Beam

Pixel sensors were bump-bonded with RD53A prototype chips² in units with 76800 single pixel cells (400 rows, 192 columns), of overall dimension 20.0mm by 11.8mm, for simplicity called "modules". We tested 25µm x 100µm and 50µm x 50µm pitch modules on 120 GeV proton beam both before and after irradiation. Preliminary results presented here were obtained with the Linear Front-End of RD53A (136 columns, from 128 to 263).



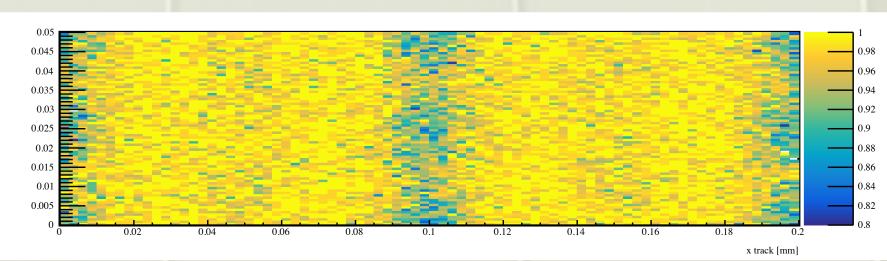


Pixel sensor (FBK). Columns are etched Active thickness **100 – 150** μm from top side only. CZ backside can be thinned down to be **Residual Handle** about 50µm thick Wafer Thickness

ionising particle creates the same number of electron-hole pairs but the max distance they have to travel before being collected is reduced from 150µm in planar to about 51µm (for 25µm x 100µm pitch 1E), 35µm (for 50µm x 50µm pitch) or down to 28µm (for 25µm x 100µm pitch 2E) in 3D pixels

- → Full depletion at lower bias voltage, especially after heavy irradiation
- → Less trapping, higher collected charge

3D Hit Efficiency before Irradiation

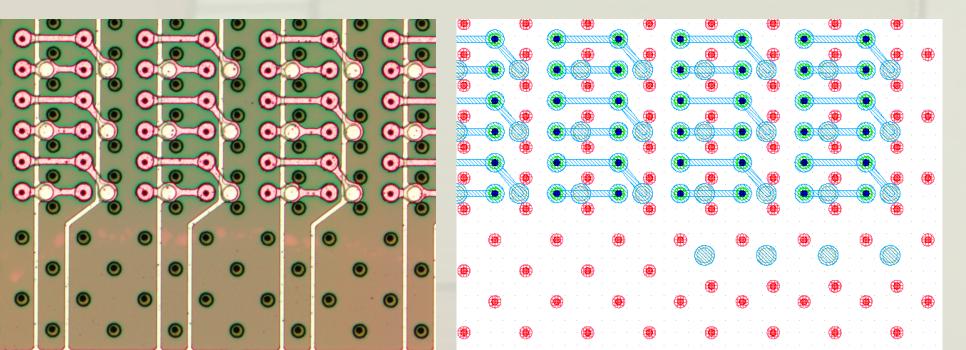


batch

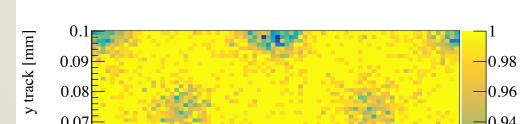
0.06

on planar test structure diode

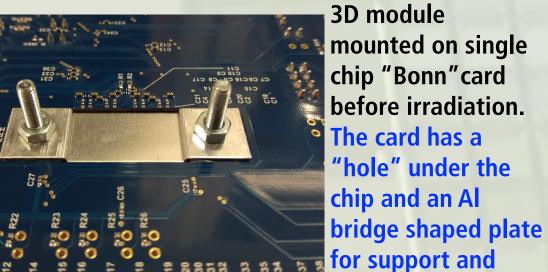
diode C-V characteristic is



3D 1E 25µm x 100µm pitch, 0 deg tilt angle, Efficiency 97.3% @ HV=3 V Depletion voltage measured



I BP



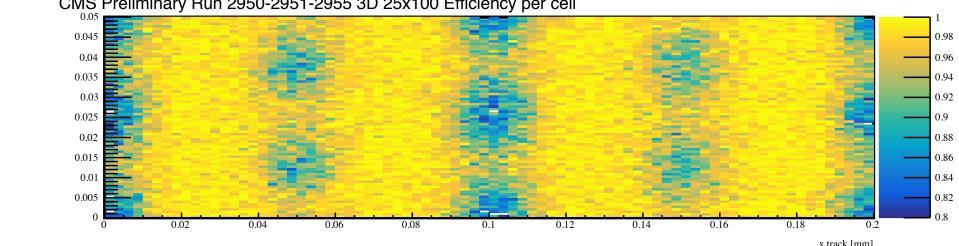
CMS Irradiation Card connected to readout adapter interface, both developed by RICE University

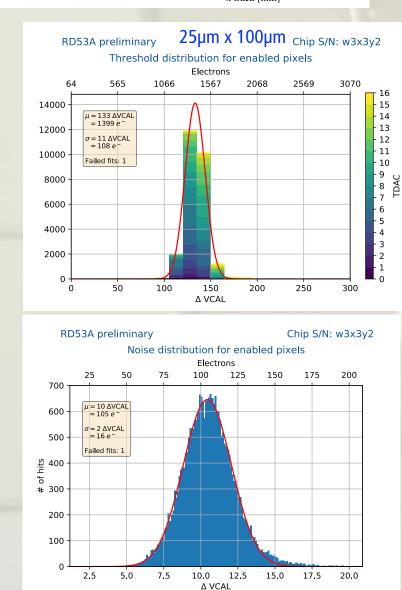


The dose for irradiated modules has been estimated to be about 6 MGy

hermal contact

3D Hit Efficiency <u>after</u> irradiation





iminary Run 2950-2951-2955 3D 25x100 Efficiency per cel

3D 1E 25µm x 100µm pitch, 0 deg tilt

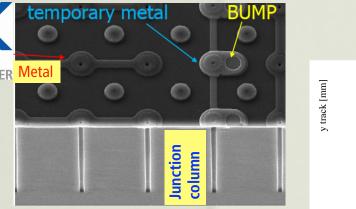
angle, Efficiency 96.6% @ HV=120 V

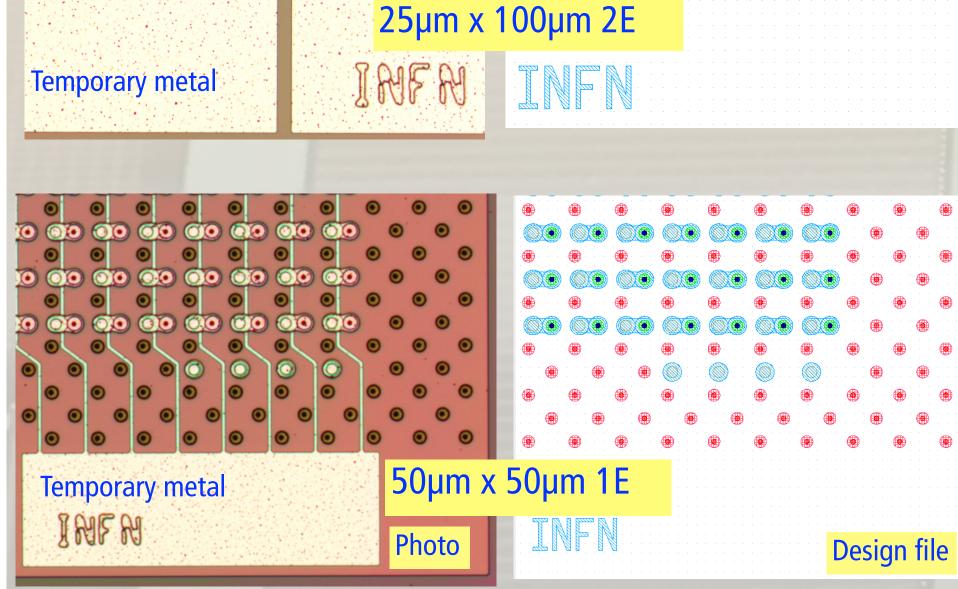
Threshold \sim 1400 e-, noise = 105 e-

Different pixels are implemented in the same wafer layout: 25µm x 100µm with two junction Electrodes (2E), 25µm x 100µm 1E, 50µm x 50µm

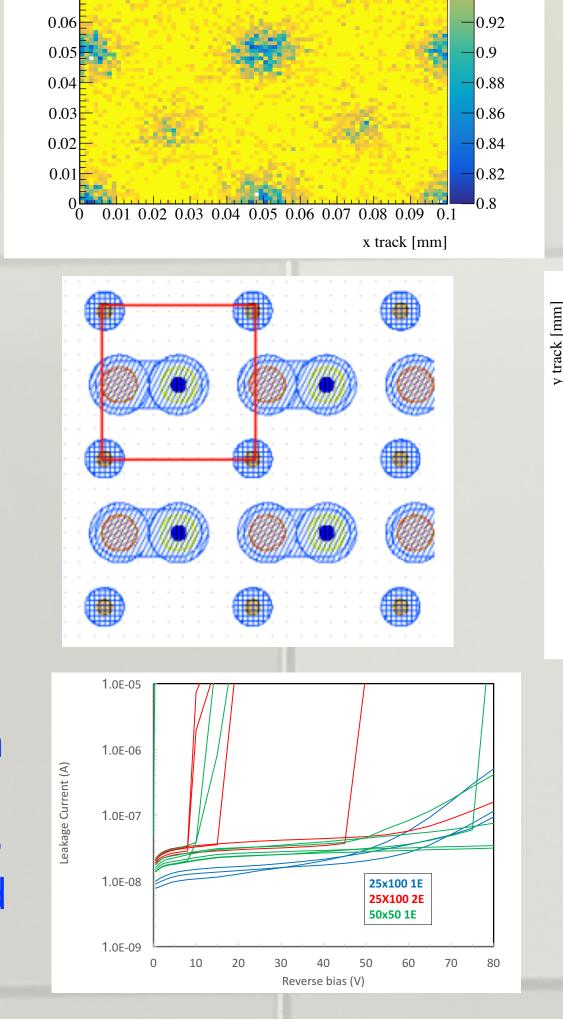
27u

SEM pictures of Ohmic columns made by Deep Reactive Ion Etching (DRIE) in SOI wafer



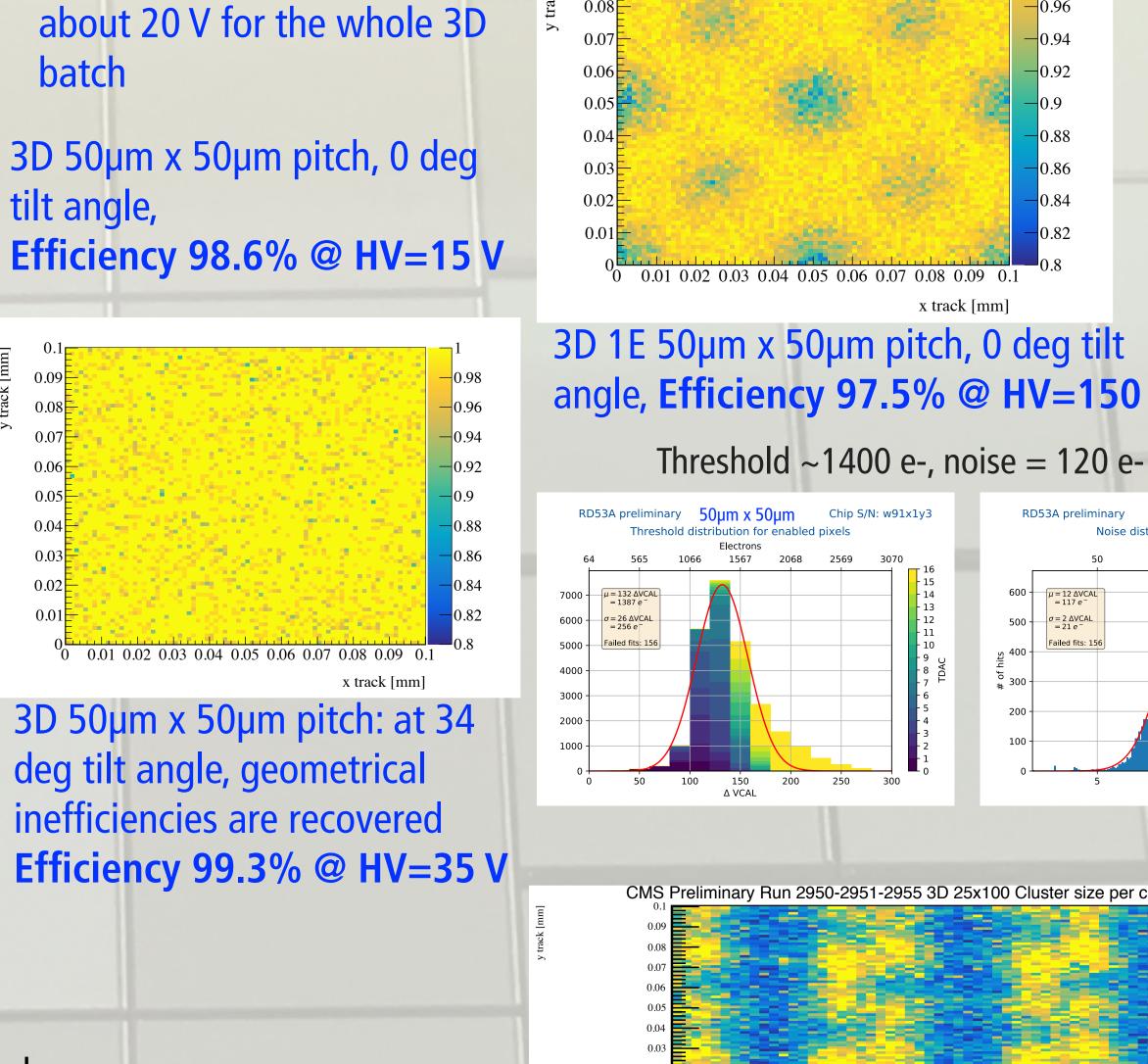


Pixel pictures taken on wafer Pixel design layouts, same scale before temporary metal removal factor as pictures Irradiations were performed at CERN IRRAD facility during summer 2018 in a high intensity 24 GeV/c proton beam, which has a FWHM of 12mm in x and y directions. The target fluence was 1x10¹⁶ neq/cm². Modules were tilted on beam at an angle of 55° to irradiate the 2.4x1cm² sensor area. Measurement and cross checks are underway in order to establish the effective fluence reached in the different zones of the modules. All results shown here are to be considered as preliminary; they are based on the assumption of the target requested equivalent fluence.

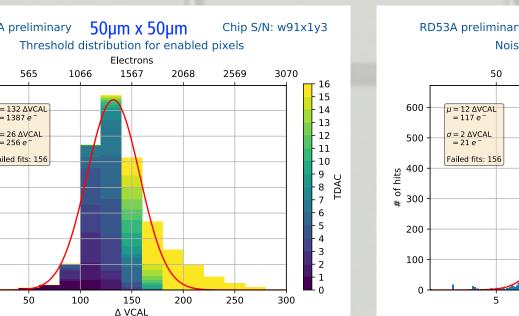


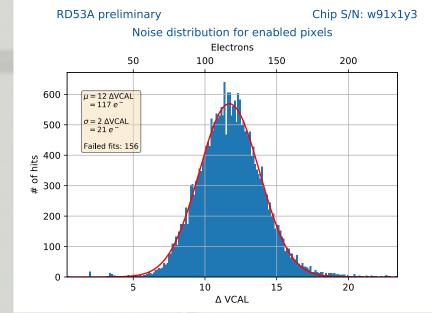
I-V Curves of 3D sensors measured on wafer using the temporary metal layer

Hit Efficiency Summary Table

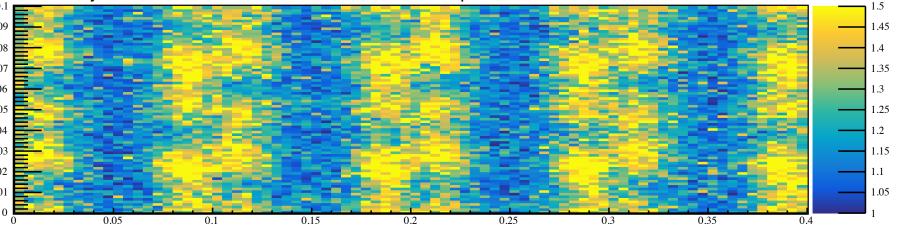


3D 1E 50µm x 50µm pitch, 0 deg tilt angle, Efficiency 97.5% @ HV=150 V





CMS Preliminary Run 2950-2951-2955 3D 25x100 Cluster size per ce



Cluster size distribution of 25µm x 100µm pixel sensor, after irradiation. Projection on 4x4 pixel cell histogram



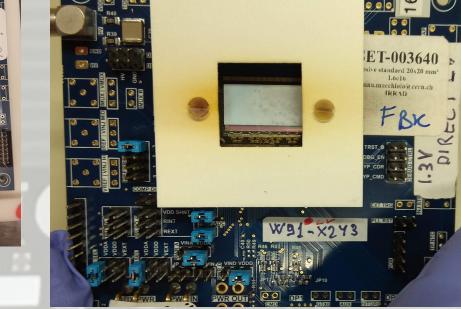
Modules mounted on the tilted

and data analysis confirm the

uniform than expected.

supports before installation in IRRAD.

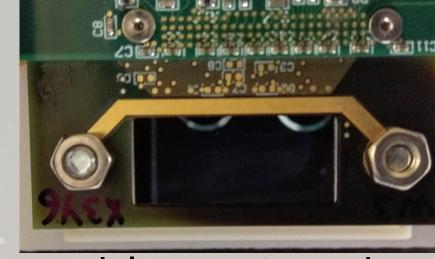
Visual inspections after irradiation



3D Pixel-RD53A	25µm x 100µm (0 deg tilt)	50µm x 50µm (0 deg tilt)
Before irradiation	97.3	98.6
After irradiation	96.6	97.5

Conclusions

Module on SCC Bonn card after irradiation



irradiation on the modules was less Module on RICE card after irradiation

Preliminary Test Beam results obtained with 3D pixel sensors show high hit efficiency both before and after irradiation at bias voltages below 200V. The same modules presented in this paper will be tested again in the Fermilab Test Beam Facility, possibly trying higher bias voltages and also RD53A analog front-ends other than Linear. New irradiations are already planned and will be done as soon as more RD53A chips will be available to build new modules. A new 3D sensors batch is in progress at FBK using Stepper process, mainly aiming at 3D sensor type 2E with 25µm x 100µm pitch.

Acknowledgements

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We thank RD53 Collaboration for the RD53A chip; we remind our results are not on chip performance but on sensor performance.

We thank Bonn ATLAS group for SCC cards and support for flip-chipping **References:**

1) Small pitch 3D devices, G.F. Dalla Betta, PoS Vertex2016 (2017) 028 2) The RD53A Integrated Circuit, Garcia-Sciveres, Maurice - CERN-RD53-PUB-17-001



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